



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s):

N. HASEGAWA, et al.

Application No.:

10/686,723

Filed:

October 17, 2003

For:

MANUFACTURING METHOD OF PHOTOMASK AND

PHOTOMASK

Expected

Group:

1756

Expected

Examiner:

K. Sagar

SUPPLEMENTAL PRELIMINARY AMENDMENT

Mail Stop Patent Application Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450 November 18, 2003

Sir:

Please amend the above-identified application, prior to examination thereof, as listed below and as set forth on the following pages:

Amendments to the Claims; and

Remarks are included following the amendments.